

BENEQ P1500

The Beneg P1500 is the world's largest ALD

reactor. With a vacuum chamber width of 1.7 meters, this tool is uniquely designed to coat very wide area substrates and large batches of 3D components. As the latest innovation in Beneg's P-Series, the P1500 continues to enable ALD on the biggest scale with viable high-volume manufacturing solutions.



Example substrates include:

- Generation 4 to 6 display glass
- Photovoltaic glass sheets
- Astronomical mirrors
- Semiconductor chamber lids, liners & showerheads
- Printed circuit boards

SIZE: Accommodate parts up to 1300×2400 mm in size or coat batches of parts in the 300 to 1000 mm size range in a reaction chamber fitted perfectly for your use case.

ENABLEMENT: The P1500 enables the introduction of ALD to applications which were not feasible before, like depositing optical coatings on astronomical mirrors.

ROBUSTNESS: Continuously switchable reaction chambers and a proprietary pre-heating oven allow users to enjoy maximum tool uptime and easy maintenance.





P1500 Specifications

PROCESS TYPE	Thermal ALD
INTEGRATION	Stand-alone
DIMENSIONS	6195×2480×2600 mm
VACUUM CHAMBER DIMENSIONS	W: 1700 mm
TEMPERATURE RANGE	25-400 °C
SUBSTRATE TYPE	Glass or metal sheets 3D and freeform parts
SUBSTRATE SPACE EXAMPLE	1300×2400×750 mm

Beneq 3D & Batch Equipment

Beneq's P-Series provides the largest scale, general purpose ALD production systems ideal for coating diverse substrate types and thick films. Easily scale up ALD deposition from the R&D phase to full manufacturing workflows.



Beneq P400A

Optimized at the intersection of deposition rate, batch size and uniformity.



Beneq P800

Perfect system for industrial batch production and manufacturing.



Beneq P1500

World's biggest ALD system for coating large substrates and batches.

